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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/630,929	07/31/2003	Eizaburo Watanabe	1186.1017D	9501
21171	7590 02/24/2005		EXAM	INER
STAAS & H.	ALSEY LLP		HODGES, MATTHEW P	
SUITE 700				
1201 NEW YORK AVENUE, N.W. WASHINGTON, DC 20005			ART UNIT	PAPER NUMBER
			2879	
			DATE MAIL ED: 02/24/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application No.	Applicant(s)				
		10/630,929	WATANABE ET AL.				
	Office Action Summary	Examiner	Art Unit				
		Matt P Hodges	2879				
Period fo	The MAILING DATE of this communication app or Reply	pears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).							
Status							
1)🛛	Responsive to communication(s) filed on 19 N	ovember 2004.					
2a) <u></u> □	This action is FINAL. 2b)⊠ This	action is non-final.					
3) 🗌	Since this application is in condition for allowance except for formal matters, prosecution as to the ments is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposit	ion of Claims						
5)	4) Claim(s) 1.2 and 11 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) Claim(s) is/are allowed.						
•	6)						
Applicat	ion Papers						
9) ☐ The specification is objected to by the Examiner. 10) ☑ The drawing(s) filed on 31 July 2003 is/are: a) ☑ accepted or b) ☐ objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority (under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 							
Attachment(s) 1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)							
2) Notic 3) Infori	te of References Cited (P10-892) te of Draftsperson's Patent Drawing Review (PT0-948) mation Disclosure Statement(s) (PT0-1449 or PT0/SB/08) tr No(s)/Mail Date	Paper No(s)/Mail Da	te atent Application (PTO-152)				

DETAILED ACTION

Response to Amendment

The Amendment, filed on 11/19/2004, has been entered and acknowledged by the Examiner.

Cancellation of claims 3-10 and 12 has been entered.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claim 11 is rejected under 35 U.S.C. 102(e) as being anticipated by Okumura et al. (US 6,100,633).

Regarding claim 11, Okumura discloses (see figure 2) a plasma display panel including, a substrate (2), an address electrode (4), and a barrier rib structure (3). The barrier rib structure is a recessed structure where the recess is formed between each of the barrier ribs. The bottom portion of the barrier rib is strait on both sides and a second portion that is tapered is formed on top of the bottom portion to form the barrier rib structure. Further there is a reflective layer (11) that reflects light from the substrate from all areas except the top of the barrier rib structure. Therefore it is inherent that the back light is at least 50% reflective to incoming light.

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Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1 and 2 are rejected under 35 U.S.C. 103(a) as being unpatentable over Asano et al. (US 5,909,083) in view of Kawai et al. (US 6,199,404).

Regarding claims 1 and 2, Asano discloses (see figure 1F) a plasma display panel including, a substrate (11), an address electrode (2), a dielectric layer (3) covering the address electrode, and a barrier rib structure (8). The barrier rib structure is a recessed structure where the recess is formed between each of the barrier ribs. The dielectric layer is 20 µm thick. (Column 17 lines 45-53). Further both the dielectric layer and the barrier rib structure are formed from compositions including low melting point glass. (Column 17 lines 25-35 and Lines 60-65). Asano does not appear to specify the use of the exact same material for the dielectric layer and the barrier rib. However Kawai, in the same field of endeavor, discloses the use of a single low-melting glass paste to form both the dielectric layer and the barrier ribs. (Column 4 lines 20-25). Kawai discloses an advanced manufacturing process that applies both the dielectric layer and the barrier ribs simultaneously to the bottom substrate. This process is advantageous over the engraving method disclosed by Asano, in that it decreases the manufacturing time and complexity. Further using a single material for both the dielectric layer and barrier ribs reduces the number of steps involved and also ensures that the bond between the barrier ribs and

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dielectric layer is strong independent of thermal expansion. Thus it would have been obvious to one having ordinary skill in the art at the time the invention was made to use a single low melting point glass for both the dielectric layer and barrier ribs as taught by Kawai in to the device as disclosed by Asano in order to advantageously decrease the manufacturing time and complexity while further reducing the number of steps involved and ensuring that the bond between the barrier ribs and dielectric layer is strong independent of thermal expansion.

Conclusion

This rejection is made non-final as a new rejection has been applied and allowable subject matter has been withdrawn.

Contact Information

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Matt P Hodges whose telephone number is (571) 272-2454. The examiner can normally be reached on 7:30 AM to 4:00 PM M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nimesh Patel can be reached on (571) 272-2457. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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JOSEPH WILLIAMS PRIMARY EXAMINER